

4066 D1/Consilium/DV

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

John F. ARACKAPARAMBIL et al.

Serial No. 10/084,092

Group Art Unit: 2121 PATENT/O

Filed: February 28, 2002

Examiner:

COMPUTER INTEGRATED MANUFACTURING TECHNIQUES For:

Technology Center 2400

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Technology Center 2100

Honorable Commissioner for Patents Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Copies of the references listed on pages 1 and 2 of Form PTO-1449 are submitted herewith.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

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to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

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Date: 9/14/02

INFORMATION DISCLOSURE CITATION IN AN APPLICATION



(PTO-1449)

ATTY. DOCKET NO. 4066 D1/Consilium/DV SERIAL NO. 10/084,092



APPLICANT

John F. ARACKAPARAMBIL et al.

FILING DATE February 28, 2002 GROUP 2121

U.S. PATENT DOCUMENTS

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October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." IBM Technical Disclosure Bulletin, pp. 2857-2860.

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						Yes	No
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GROUP GROUP February 28, 2002

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